## Standard Oxide Etch Recipe Vision RIE 2

March 28, 2013

## Equipment

Equipment Vision RIE 2

Manufacture Advanced Vacuum Model Vision-320 RIE

Platen size 12 in Platen Material Graphite

## Recipe

Recipe Name Standard Oxide

Gas CHF<sub>3</sub> 45 sccm

O<sub>2</sub> 5 sccm

Platen Power 250 W

RF Frequency 13.56 Mhz Chamber Pressure 40 mTorr

## Results <sup>a</sup>

Material Thermo Oxide (Grown @ 1050 °C)

Etch Rate 217.7 A/min <sup>b</sup>

Uniformity 1.66 % <sup>c</sup>

Mask: Microposit SC1827 d

Selectivity (vs. PR) 3.61:1

a: All data is updated as the date indicated above

b: An average value from 15 min etch

c: Etching depth variation across a 4" wafer, defined as std/average

d: Photo-resist was pre-baked @115 °C for 40 sec on a hotplate